

IN THE CLAIMS:

Please cancel claims 1-26 and add new claims 27-51 as follows:

1-26. (Canceled)

27. (New) A method of manufacturing an electro-optical device comprising:

providing a substrate by a substrate holder in film formation chamber;

forming a film comprising an organic material over the substrate by vapor deposition in the film formation chamber wherein said organic material is simultaneously deposited on said substrate holder;

removing said substrate from said reaction chamber after forming said film;

irradiating a component provided in a film-forming chamber with a light selected from the group consisting of infrared light, UV-light, and visible light, thereby sublimating a vapor deposition material adhering to the component; and

exhausting the sublimated vapor deposition material,

wherein the vapor deposition material comprises an organic light emitting material.

28. (New) A method of manufacturing a light emitting device comprising:

providing a substrate by a substrate holder in film formation chamber;

forming a film comprising an organic material over the substrate by vapor deposition in the film formation chamber wherein said organic material is simultaneously deposited on said substrate holder;

removing said substrate from said reaction chamber after forming said film;

irradiating a component provided in a film-forming chamber with a light selected from the group consisting of infrared light, UV-light, and visible light, thereby sublimating a vapor deposition material adhering to the component; and

exhausting the sublimated vapor deposition material,

wherein the vapor deposition material comprises an organic light emitting material.

29. (New) The method according to claim 27, wherein said light selected from the group consisting of the infrared light, UV-light, and visible light is radiated by using a light source provided in the film-forming chamber.

30. (New) The method according to claim 27, wherein an irradiation surface of said light selected from the group consisting of the infrared light, UV-light, and visible light is in a rectangular or oblong shape.

31. (New) The method according to claim 27, further comprising a step of supplying a halogen containing gas into the film-forming chamber during sublimating the vapor deposition material.

32. (New) The method according to claim 27, further comprising a step of forming a plasma during exhausting.

33. (New) The method according to claim 32, wherein said plasma is an oxygen plasma.

34. (New) The method according to claim 28, wherein said light selected from the group consisting of the infrared light, UV-light, and visible light is radiated by using a light source provided in the film-forming chamber.

35. (New) The method according to claim 28, wherein an irradiation surface of said light selected from the group consisting of the infrared light, UV-light, and visible light is in a rectangular or oblong shape.

36. (New) The method according to claim 28, further comprising a step of supplying a halogen containing gas into the film-forming chamber during sublimating the vapor deposition material.

37. (New) The method according to claim 28, further comprising a step of forming a plasma during exhausting.

38. (New) The method according to claim 37, wherein said plasma is an oxygen plasma.

39. (New) A method of manufacturing a display device comprising:
providing a substrate by a substrate holder in a film formation chamber;
forming a film comprising an organic material over the substrate by vapor deposition in the film formation chamber wherein said organic material is simultaneously deposited on said substrate holder;
removing said substrate from said reaction chamber after forming said film;
heating said organic material deposited on said substrate holder in said film formation chamber to vaporize said organic material;
exhausting the vaporized organic material from said film formation chamber.

40. (New) The method according to claim 39, wherein said film comprising an organic material is a light emitting layer.

41. (New) The method according to claim 39, further comprising a step of supplying a halogen containing gas into the film formation chamber during heating said organic material.

42. (New) The method according to claim 39, further comprising exposing the vaporized organic material to a plasma.

43. (New) A method of manufacturing a display device comprising:
providing a substrate by a substrate holder in a film formation chamber wherein an adhesion preventing shield is provided between said substrate and an inner wall of the film formation chamber;
forming a film comprising an organic material over the substrate by vapor deposition in the film formation chamber wherein said organic material is simultaneously deposited on said adhesion preventing shield;
removing said substrate from said reaction chamber after forming said film;

heating said adhesion preventing shield to vaporize said organic material deposited on said adhesion preventing shield;

exhausting the vaporized organic material from said film formation chamber.

44. (New) The method according to claim 43, wherein said film comprising an organic material is a light emitting layer.

45. (New) The method according to claim 43, further comprising a step of supplying a halogen containing gas into the film formation chamber during heating said organic material.

46. (New) The method according to claim 43, further comprising exposing the vaporized organic material to a plasma.

47. (New) A method of manufacturing an electro-optical device comprising:
providing a substrate by a substrate holder in film formation chamber;
forming a film comprising an organic material over the substrate by vapor deposition in the film formation chamber wherein said organic material is simultaneously deposited on said substrate holder;
removing said substrate from said reaction chamber after forming said film;
irradiating a component provided in a film-forming chamber by scanning a lamp light source, thereby sublimating a vapor deposition material adhering to the component; and
exhausting the sublimated vapor deposition material,
wherein the vapor deposition material comprises an organic light emitting material.

48. (New) The method according to claim 47, wherein the lamp light source is selected from the group consisting of infrared light, UV-light, and visible light.

49. (New) The method according to claim 47, further comprising a step of supplying a halogen containing gas into the film-forming chamber during sublimating the vapor deposition material.

50. (New) The method according to claim 47, further comprising a step of forming a plasma during exhausting.

51. (New) The method according to claim 50, wherein said plasma is an oxygen plasma.